Title	Three-dimensional deposition of TiN film using low frequency (50 Hz) plasma chemical vapor deposition
Author(s)	Shimozuma, M.; Date, H.; Iwasaki, T.; Tagashira, H.; Yoshino, M.; Yoshida, K.
Citation	Journal of Vacuum Science & Technology. A, Vacuum, Surfaces, and Films, 15(4), 1897-1901 https://doi.org/10.1116/1.580657
Issue Date	1997-07
Doc URL	http://hdl.handle.net/2115/5732
Type	article
Note	Erratum: Journal of Vacuum Science & Technology. A, Vacuum, Surfaces, and Films. 15(6), 1997, p.3170, DOI: 10.1116/1.580863
Additional Information	There are other files related to this item in HUSCAP. Check the above URL.
File Information	JOVS&TA-VSA15-6.pdf (Erratum)

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Erratum: "Three-dimensional deposition of TiN film using low frequency (50 Hz) plasma chemical vapor deposition" [J. Vac. Sci. Technol. A 15, 1897 (1997)]

M. Shimosuma^{a)} and H. Date

College of Medical Technology, Hokkaido University, Sapporo 060, Japan

T. Iwasaki and H. Tagashira

Department of Electrical Engineering, Hokkaido University, Sapporo 060, Japan

M. Yoshino

Hokkaido Polytechnic College, Zenibako 3-190, Otaru 047-02, Japan

K. Yoshida

Department of Electrical and Electronic Engineering, Kitami Institute of Technology, Kitami 090, Japan

[S0734-2101(98)01501-2]

Due to an error in production, Fig. 1 was incorrectly printed. The correct figure is published below.

FIG. 1. Schematic diagram of the plasma CVD apparatus with substrate bias circuit using two diodes.

^{a)}Electronic mail: smzm@cme.hokudai.ac.jp